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Generation of the CF₃ radical from trifluoromethylsulfonium triflate and its trifluoromethylation of styrenes†Cheng-Pan Zhang,^a Zong-Ling Wang,^{ab} Qing-Yun Chen,^a Chun-Tao Zhang,^b Yu-Cheng Gu^c and Ji-Chang Xiao^{*a}

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The CF₃ radical was generated from the reaction of *S*-(trifluoromethyl)diphenylsulfonium triflate with Na₂S₂O₄ or HOCH₂SO₂Na under suitable conditions without further reduction. Based on this, a method for the synthesis of α -trifluoromethylated ketones has been successfully developed.

Trifluoromethylated compounds are increasingly important in organic and medicinal chemistry.¹ A series of trifluoromethylating reagents have been designed and synthesized to transfer the trifluoromethyl group into organic compounds.^{1,2} *S*-(Trifluoromethyl)diarylsulfonium salts, which were first prepared by Yagupolskii and then developed by Umemoto, Shreeve, Ishihara and Shibata, have been successfully used for the electrophilic trifluoromethylation of nucleophiles.³ To the best of our knowledge, however only few novel applications beyond the electrophilic reactions of these trifluoromethylating reagents have been published so far.^{3–5} In our previous work, we found that *S*-(trifluoromethyl)diphenylsulfonium triflate could be reduced by metals.^{5b} On the basis of this observation, we developed a convenient method for the synthesis of trifluoromethylated heteroaromatics under mild conditions using an *S*-(trifluoromethyl)diphenylsulfonium salt and copper as the reagent mixture.^{5b} The intermediacy of a CuCF₃ species was confirmed in this trifluoromethylation reaction, and the CF₃ radical (\cdot CF₃) was assumed to be the most probable precursor to the CF₃ anion (CF₃[−]), although it could not be captured by radical acceptors when metals were present in the reaction mixture.

In order to obtain the CF₃ radical and to avoid its further reduction and thus expand its application, we investigated the reaction of *S*-(trifluoromethyl)diphenylsulfonium triflate with the reducing agents Na₂S₂O₄ and HOCH₂SO₂Na.⁶ We were pleased to find that the CF₃ radical generated from the trifluoromethylsulfonium salt had a sufficient lifetime to be

captured by styrenes. This is the first example of the generation of the CF₃ radical from a trifluoromethylsulfonium salt initiated by Na₂S₂O₄ or HOCH₂SO₂Na. Herein, we report the details.

As shown in Table 1, *S*-(trifluoromethyl)diphenylsulfonium triflate reacted with styrene at room temperature or at 0 °C in the presence of two equivalents of Na₂S₂O₄ to provide **2a** in 26% yield (entries 1 and 2, Table 1). This product is completely different from that obtained in the reaction between olefins and the CF₃ radical derived from CF₃I and Na₂S₂O₄, SmI₂ or Et₃B.^{6g–k} The reaction temperature and the amount of reductant influence the reaction. For example, reducing the reaction temperature to −15 °C, gave the desired product **2a** in a lower 19% yield (entry 3, Table 1), and using one instead of two equivalents of Na₂S₂O₄ gave the product **2a** in only 14% yield (entry 4, Table 1). Similar results were found in the reaction of **1a** with *S*-(trifluoromethyl)diphenylsulfonium triflate and HOCH₂SO₂Na·2H₂O (entries 9–11, Table 1). The use of larger excesses of HOCH₂SO₂Na·2H₂O from 6 equiv. to 11 equiv. in this reaction, however, led to no increase in the yield of **2a** (entries 12 and 13, Table 1). The amount of the sulfonium salt also has an influence on the reaction (entries 11–14, Table 1). For example, treatment of *S*-(trifluoromethyl)diphenylsulfonium triflate (2 equiv.) with **1a** (1 equiv.) in the presence of HOCH₂SO₂Na·2H₂O (6 equiv.) at 0 °C afforded **2a** in 36% yield (entry 12, Table 1), while the use of three equivalents of the sulfonium salt under the same conditions provided **2a** in 42% yield (entry 14, Table 1). Moreover, the use of an excess of styrene in this reaction resulted in a 40% yield of the product (entry 15, Table 1).

Besides the generation of **2a**, CF₃H and CF₃CF₃ were formed in these reactions (CF₃SO₂Na could not be completely excluded, however). The presence of these by-products was determined by ¹⁹F NMR spectra according to a literature method.⁷ No residual styrene **1a** was detected by TLC and GC analysis of the reaction mixtures, except for the reaction shown as entry 15 in Table 1. The polymerization of styrene might occur under the reaction conditions, leading to a complete loss of **1a**. The formation of CF₃H and CF₃CF₃ is important evidence that the CF₃ radical is generated from *S*-(trifluoromethyl)diphenylsulfonium triflate and is not further reduced to the CF₃ anion by Na₂S₂O₄ or HOCH₂SO₂Na.

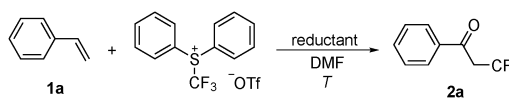
^a Key Laboratory of Organofluorine Chemistry, Shanghai Institute of Organic Chemistry, Chinese Academy of Sciences, 345 Lingling Road, Shanghai 200032, China.

E-mail: jchxiao@mail.sioc.ac.cn; Fax: (+86) 21-64166128

^b Hunan University of Chinese Medicine, Changsha, Hunan Province 410208, China

^c Syngenta, Jealott's Hill International Research Centre, Bracknell, Berkshire, RG42 6EY, UK

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Table 1 Screening for optimal conditions for the oxidative-trifluoromethylation of styrene^a


Entry	Reductant (R)	1a : [Ph ₂ SCF ₃] ⁺ [OTf] ⁻ : R ^b	Time (h)	T/°C	Yield (2a , %) ^c
1	Na ₂ S ₂ O ₄	1 : 1 : 2	5	r.t.	26
2	Na ₂ S ₂ O ₄	1 : 1 : 2	6	0	26
3	Na ₂ S ₂ O ₄	1 : 1 : 2	6	-15	19
4	Na ₂ S ₂ O ₄	1 : 1 : 1	11	r.t.	14
5 ^d	Na ₂ S ₂ O ₄	1 : 1 : 2	5	r.t.	14
6 ^e	Na ₂ S ₂ O ₄	1 : 1 : 2	6	0	14
7 ^f	Na ₂ S ₂ O ₄	1 : 1 : 2	6	0	22
8 ^g	Na ₂ S ₂ O ₄	1 : 1 : 2	5	r.t.	0
9	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 2	5	r.t.	22
10	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 2	5	0	28
11	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 3	5	0	34
12	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 2 : 6	5	0	36
13	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 2 : 11	5	0	36
14	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 3 : 6	5	0	42
15	HOCH ₂ SO ₂ Na·2H ₂ O	4 : 1 : 3	6	0	40

^a The reaction was conducted in air. ^b Molar ratio. ^c Determined by ¹⁹F NMR and TLC analysis. ^d 6 equivalents of H₂O were added. ^e 6 equivalents of H₂O¹⁸ were added. ^f The solvent was dried. ^g The reaction was conducted under a nitrogen atmosphere.

Although we have made extensive efforts to try to improve the yield of **2a**, the generation of CF₃H and CF₃CF₃ and the polymerization of styrene could not be completely suppressed. In fact, α-trifluoromethylated ketones (e.g. RCOCH₂CF₃) are difficult to synthesize.⁸ Ando *et al.* reported that treatment of α,β-unsaturated ketones with CF₃I in the presence of Et₂Zn and RhCl(PPh₃)₃ could give α-trifluoromethylation products in moderate yield.^{8b} Furthermore, trimethyl(1-phenylvinyl)oxy-silane reacts with CF₃I in the presence of RhCl(PPh₃)₃ to provide **2a** in 32% yield.^{8c} The requirement for an expensive catalyst limits the use of these methods, making the methodology that we report in this paper highly significant.

Reductants such as Na₂SO₃, NaHSO₃, P(NEt₂)₃ and P(OEt)₃ were also tested for their suitability in the reaction. However, none of the desired product was formed in most cases, as determined by ¹⁹F NMR spectroscopy and TLC analysis (entries 1–4, Table 2). When Na₂S₂O₃·5H₂O was used as the reductant, **2a** was obtained in 11% yield, which is lower than the yields obtained with Na₂S₂O₄ or HOCH₂SO₂Na·2H₂O.

It was also found that the solvent greatly influenced the reaction. When DMF was replaced by DMSO, MeOH, THF or acetone, only a trace of **2a** was formed (entries 6, 8, 10 and 12, Table 2), while none of the required product was formed when CH₃CN, H₂O or DCM were used as the solvent (entries 7, 9 and 11, Table 2). This indicated that DMF is the most suitable solvent for the reaction.


To explore the scope of the reaction, as well as its suitability for the preparation of substituted α-trifluoromethylated ketones, various styrenes were allowed to react with S-(trifluoromethyl)diphenylsulfonium triflate in the presence of HOCH₂SO₂Na·2H₂O. As shown in Table 3, styrenes with electron-withdrawing and electron-donating groups on the phenyl ring were all transformed into the corresponding oxidative-trifluoromethylation products (entries 1–9, Table 3). The position of the substituent had some influence on the reaction. On replacement of the *meta*-substituted styrene (**1b**) with the *para*-substituted analogue (**1c**), the oxidative-trifluoromethylated product (**2c**) was obtained in higher yield (entries 1 and 2, Table 3). When *ortho*-nitro-substituted styrene was used instead of **1b**, almost none of the desired product was obtained (not shown). 1-Vinylnaphthalene was also found to be a suitable substrate for this reaction. (entry 10, Table 3). Aliphatic olefins do not seem to be suitable substrates for this reaction (e.g. entry 11, Table 3).

Based on the results achieved above, we propose the following mechanism for the reaction (Scheme 1). The S-(trifluoromethyl)diphenylsulfonium triflate is first reduced by Na₂S₂O₄ or HOCH₂SO₂Na via single electron transfer (SET) to form the intermediate **3**.^{6k} The CF₃ radical is then formed via rapid decomposition of intermediate **3** and can be captured by styrenes to give **4** with hardly any over-reduction to form the CF₃ anion. Finally, the intermediate **4** is oxidized to produce the observed product. As expected, Ph₂S was formed in the reaction and could be isolated by column chromatography after workup. The final step in this sequence, an oxidative process, surprised us because it unexpectedly happened in the presence of Na₂S₂O₄ or HOCH₂SO₂Na which are always used as reductants. Moreover, the addition of six equivalents of water to the reaction mixture of **1a** with S-(trifluoromethyl)diphenylsulfonium triflate and Na₂S₂O₄ led to a lower yield of the product (entry 5, Table 1), while the addition of H₂O¹⁸ instead of H₂O led to a product which did not contain an O¹⁸ atom (entry 6, Table 1). When the

Table 2 Reductants and solvents used for the oxidative-trifluoromethylation of styrene^a

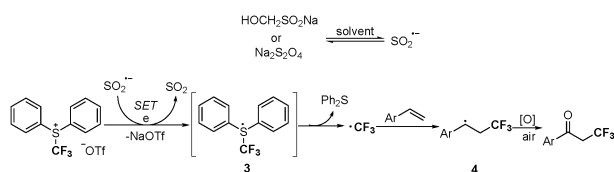
Entry	Reductant (R)	1a : [Ph ₂ SCF ₃] ⁺ [OTf] ⁻ : R ^b	Solvent	Time (h)	T/°C	Yield (2a , %) ^c
1	Na ₂ SO ₃	1 : 1 : 2	DMF	5	r.t.	Trace
2	NaHSO ₃	1 : 1 : 2	DMF	5	r.t.	0
3	P(NEt ₂) ₃	1 : 1 : 2	DMF	6	r.t.	0
4	P(OEt) ₃	1 : 1 : 2	DMF	6	r.t.	0
5	Na ₂ S ₂ O ₃ ·5H ₂ O	1 : 1 : 2	DMF	5	r.t.	11
6	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 3	DMSO	5	0	Trace
7	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 3	CH ₃ CN	5	0	0
8	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 3	MeOH	5	0	Trace
9	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 3	H ₂ O	5	0	0
10	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 3	THF	5	0	Trace
11	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 3	DCM	5	0	0
12	HOCH ₂ SO ₂ Na·2H ₂ O	1 : 1 : 3	Acetone	5	0	Trace

^a The reaction was conducted in air. ^b Molar ratio. ^c Determined by ¹⁹F NMR and TLC analysis.

Table 3 The oxidative-trifluoromethylation of styrenes^a


Entry	Ar	Yield (%) ^b
1	<i>m</i> -NO ₂ C ₆ H ₄ (1b)	21 (2b)
2	<i>p</i> -NO ₂ C ₆ H ₄ (1c)	25 (2c)
3	<i>m</i> -PhC ₆ H ₄ (1d)	23 (2d)
4	<i>p</i> -PhC ₆ H ₄ (1e)	33 (2e)
5	<i>o</i> -ClC ₆ H ₄ (1f)	21 (2f)
6	<i>p</i> -ClC ₆ H ₄ (1g)	31 (2g)
7	<i>p</i> -BrC ₆ H ₄ (1h)	30 (2h)
8	<i>p</i> -MeC ₆ H ₄ (1i)	31 (2i)
9	<i>p</i> -MeOC ₆ H ₄ (1j)	39 (2j)
10	1-Naphthyl (1k)	31 (2k)
11	<i>n</i> -C ₈ H ₁₇ (1l)	Complex

^a The molar ratio of **1b-l**: [Ph₂SCF₃]⁺[OTf]⁻: HOCH₂SO₂Na·2H₂O is 1 : 2 : 6. ^b Isolated yield.

**Scheme 1** Proposed mechanism for the oxidative-trifluoromethylation of styrenes by *S*-(trifluoromethyl)diphenylsulfonium salt.

reaction was run under a nitrogen atmosphere, however, none of the product was formed (entry 8, Table 1). It seems that the oxygen atom in these products comes from O₂.

In summary, we have discovered that *S*-(trifluoromethyl)diphenylsulfonium triflate can react with Na₂S₂O₄ or HOCH₂SO₂Na under suitable conditions to generate the CF₃ radical without further reduction. Based on this, a convenient method for the synthesis of α -trifluoromethylated ketones has been successfully developed. We propose that the *S*-(trifluoromethyl)diphenylsulfonium triflate is reduced by Na₂S₂O₄ or HOCH₂SO₂Na via a SET mechanism, and that the CF₃ radical is the key intermediate which reacts with styrene to produce, after oxidation, α -trifluoromethylated ketones. Investigations into the details of the oxidation process in this reaction are currently underway.

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